

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	7690	"dual damascene" or (dual with damascene)	US_PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/22 11:07
L4	1128	(resist or photoresist) same (via or contact or trenches) same (ARC or BARC or "anti-reflective")	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:10
L5	245	1 and 4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:10
L6	206	(resist or photoresist) same (via or contact or trenches) same (ARC or BARC or "anti-reflective") same (wiring or conductive)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:11
L7	5302	(resist or photoresist) and (via or contact or trenches) and (ARC or BARC or "anti-reflective") and (wiring or conductive)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:13
L8	421	7 and 1	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:12
L9	1	keum-dong-yeal.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:13
L10	4198	(resist or photoresist) and (via or contact or trenches) and (ARC or BARC or "anti-reflective") and (wiring or conductive) and (mask\$4 or pattern\$4)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:14
L11	2890	10 and semiconductor	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:14
L12	539	11 and damascene	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 11:14